

Abstract:

The present invention relates to an illumination system for microlithography,  
5 especially for wavelengths  $\leq 193$  nm, especially preferably for EUV lithography for  
illuminating a field in a field plane with at least one optical integrator which splits  
up a light bundle emitted by a light source into a plurality of light channels each  
having a light intensity,  
characterized in that  
10 a filter is provided in the light path from the light source to the field plane, with the  
filter comprising filter elements which are configured in such a way that the light  
intensity of at least one light channel is reduced in the light path after the filter  
element.

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